

U.S. Department of Commerce, Patent and Trademark Office		Docket No.	Serial No.
		AMAT/3577/PDD/KPU1/JW	Unknown
LIST OF REFERENCES CITED BY APPLICANT		Applicant <i>attach to #2</i>	
(Use several sheets if necessary)		Judy Huang	
BEST AVAILABLE COPY		Filing Date	Group
		Herewith <i>6/18/97</i>	Unknown <i>1762</i>

U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
<i>MSP</i>	AA	5,821,603	10/13/1998	Puntambekar	257	640	05/29/1996
	AB	5,801,098	09/01/1998	Fiordalice et al.	438	653	09/03/1996
	AC	5,780,163	07/14/1998	Camilletti et al.	428	446	06/05/1996
	AD	5,660,682	08/26/1997	Zhao et al.	438	715	03/14/1996
	AE	5,512,512	04/30/1996	Isobe	437	187	11/30/1993
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	AH	4,994,410	02/19/1991	Sun et al.	437	192	02/16/1990
<i>MSP</i>	AI	4,980,196	12/25/1990	Yasuda et al.	427	38	02/14/1990

Foreign Patent Documents

Translation

		Document Number	Date	Country	Class	Subclass	Yes	No
	AL							

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>MSP</i>	AM	K. Mikagi, H. Ishikawa, T. Usami, M. Suzuki, K. Inoue, N. Oda, S. Chikaki, I. Sakai and T. Kikkawa, "Barrier Metal Free Copper Damascene Interconnection Technology Using Atmospheric Copper Reflow and Nitrogen Doping in SiOF Film," © 1996 IEEE, IEDM 96 365-368, Pages 14.5.1-14.5.4 <i>1996 - no month</i>						
<i>MSP</i>	AN	S. S. Wong, C. G. Sodini, T. W. Ekstedt, H. R. Grinolds, K. H. Jackson and S. H. Kwan, "Low Pressure Nitrided-Oxide as a Thin Gate Dielectric for MOSFET's," J. Electrochem Soc.: SOLID-STATE SCIENCE AND TECHNOLOGY, Vol. 130, No. 5, May, 1983, Pages 1139-1143						
<i>MSP</i>	AO	Takahi Ito, Takao Nozaki, and Hajime Ishikawa, "Direct Thermal Nitridation of Silicon Dioxide Films in Anhydrous Ammonia Gas," Optical Properties, Vol. 127, No. 9, September, 1980, Pages 2053-2057						

Examiner <i>M. J. Polgott</i>	Date Considered <i>9/27/00</i>
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

U.S. Department of Commerce, Patent and Trademark Office					Docket No.		Serial No. 071	
					AMAT/3577/PDD/KPU1/JW		Unknwon 336,525	
LIST OF REFERENCES CITED BY APPLICANT					Applicant			
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*Examiner Initial		Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate	
	BA	4,510,178	04/09/1985	Paulson et al.	427	94	02/14/1983	
	BB	4,420,386	12/13/1983	White	204	192	04/22/1983	
	BC							
	BD							
	BE							
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Foreign Patent Documents								
		Document Number	Date	Country	Class	Subclass	Yes	No
	BL							
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	BM	Richard Swope, Woo Sik Yoo, Julian Hsieh, Shari Shuchmann, Ferenc Nagy, Harald te Nijenhuis, and David Mordo, "Improvement of Adhesion Properties of Fluorinated Silica Glass Films by Nitrous Oxide Plasma Treatment," J. Electrochem. Soc., Vol. 144, No. 7, July, 1997, The Electrochemical Society, Inc., Pages 2559-2564						
	BN	S. Takeishi, H. Kudoh, R. Shinohara, A. Tsukune, Y. Sotoch, H. Miyazawa, H. Harada, and M. Yamada, "Stabilizing Dielectric Constants of Fluorine-Doped SiO ₂ Films by N ₂ O-Plasma Annealing," J. Elelctrochem. Soc., Vol. 143, No. 1, January, 1996, The Electrochemical Society, Inc., Pages 381-385						
	BO							
	BP							
	BQ							
Examiner		Date Considered 9/27/00						
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